

UNITED STATES DEPARTMENT OF COMMERCE

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APPLICATION NO. **FILING DATE** FIRST NAMED INVENTOR ATTORNEY DOCKET NO. 09/492,243 01/27/00 HE M-7469-US **EXAMINER** 024251 MM91/1025 SKJERVEN MORRILL MACPHERSON LLP ORTIZ.E PAPER NUMBER 25 METRO DRIVE **ART UNIT** SUITE 700 SAN JOSE CA 95110 2815 **DATE MAILED:**

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

10/25/01

Office Action Summary

Application No. 09/492,243 Applicant(s)

He Et.al.

Examiner

Edgardo Ortiz

Art Unit 2815



	The IVIAILING DATE of this communication appears	s on the cover si	eet with	the correspondence address
	for Reply			
	ORTENED STATUTORY PERIOD FOR REPLY IS SE MAILING DATE OF THIS COMMUNICATION.	T TO EXPIRE _	3	MONTH(S) FROM
- Extensions of time may be available under the provisions of 37 CFR 1.136 (a). In no event, however, may a reply be timely filed				
- If the	ter SIX (6) MONTHS from the mailing date of this communi period for reply specified above is less than thirty (30) day		he statut	ory minimum of thirty (30) days will
- If NO	considered timely. period for reply is specified above, the maximum statutory	period will apply	and will e	expire SIX (6) MONTHS from the mailing date of thi
- Failu	mmunication. e to reply within the set or extended period for reply will, b			
	reply received by the Office later than three months after th rned patent term adjustment. See 37 CFR 1.704(b).	e mailing date of	this comr	nunication, even if timely filed, may reduce any
Status	B	004		
1) 💢	Responsive to communication(s) filed on Oct 9, 20			•
2a) 🗌	This action is FINAL . 2b) 💢 This ac	tion is non-fina	l.	
3) 🗆	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11; 453 O.G. 213.			
-	tion of Claims			
4) X	Claim(s) <u>1-4 and 9-12</u>			is/are pending in the application.
4	la) Of the above, claim(s)	******		is/are withdrawn from consideration.
5) 🗆	Claim(s)			is/are allowed.
6) 💢	Claim(s) 1-4 and 9-12			is/are rejected.
7) 🗌	Claim(s)		. <u> </u>	is/are objected to.
8) 🗆	Claims	are	e subjec	t to restriction and/or election requirement.
Applica	tion Papers			
9) 🗆	The specification is objected to by the Examiner.			
10)	The drawing(s) filed on is/ard	e objected to by	the Ex	aminer.
11) ☐ The proposed drawing correction filed on is: a) ☐ approved b) ☐ disapproved.				
12)	The oath or declaration is objected to by the Exam	niner.		
Priority	under 35 U.S.C. § 119			
13) Acknowledgement is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d).				
a)] All b) ☐ Some* c) ☐ None of:			
	1. Certified copies of the priority documents have been received.			
	2. \square Certified copies of the priority documents have			
	3. Copies of the certified copies of the priority of application from the International Burese the attached detailed Office action for a list of the action for a list	eau (PCT Rule 1	7.2(a)).	_
 14)□	Acknowledgement is made of a claim for domestic	•		
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Attachm				
	stice of References Cited (PTO-892)			O-413) Paper No(s).
	ormation Disclosure Statement(s) (PTO-1449) Paper No(s).	19) Notice of In	tormal Pate	nt Application (PTO-152)
- 24	The state of the s	_5, 5.nor.		

DETAILED ACTION

This Office Action is in response to an election filed October 9, 2001 on which Applicant elected Group I (Claims 1-4 and 9-12).

Claim Rejections - 35 USC § 102

1 The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless --

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-4 and 9-12 are rejected 35 § 102 (b) as being anticipated by Chen et.al. (U.S. Patent No. 5,045,898). With regard to Claim 1, Chen teaches a plurality of floating gate transistors connected in series, each floating gate transistor formed in a well of a semiconductor substrate (51), source and drain (55) regions and a channel regions separating said source and drain regions, said channel with a non-uniform concentration of dopant (boron).

With regard to Claim 2, Chen teaches a non-uniform concentration comprising a retrograde concentration distribution in the direction from the surface of the substrate.

With regard to Claim 3, Chen teaches a non-uniform concentration comprising a lateral concentration distribution along the length of the channel that is higher in a region generally

towards the central portion of the channel region and decreases toward the source and drain regions.

With regard to Claim 4, Applicant claims that "the non-uniform concentration is formed by a tilted ion implantation utilizing as a mask a gate structure of each floating gate NMOS transistor." This a product by process limitation. A "product by process" claim is directed to the product per se, no matter how actually made, In re Brown, 173 USPQ 685; In re Luck, 177 USPQ 523; In re Fessmann, 180 USPQ 324; In re Avery, 186 USPQ 161, In re Wertheim, 191 USPQ 90 (209 USPQ 554 does not deal with this issue), In re Marosi et al, 218 USPQ 289; and particularly In re Thorpe, 227 USPQ 964, all of which make it clear that it is the patentability of the final product per se which must be determined in a "product by process" claim, and not the patentability of the process, and that an old or obvious product produced by a new method is not patentable as a product, whether claimed in "product by process" claims or not. Note that applicant has the burden of proof in such cases, as the above case law makes clear.

With regard to Claim 9, Chen teaches an isolated gate floating gate NMOS transistor comprising in well structure of a substrate (51), a source and drain region (55) and a channel region separating the source and drain regions, said channel region an non-uniform concentration of a dopant (boron).

With regard to Claim 10, Chen teaches a non-uniform concentration comprising a retrograde concentration distribution in the direction from the surface of the substrate.

With regard to Claim 11, Chen teaches a non-uniform concentration comprising a lateral concentration distribution along the length of the channel that is higher in a region generally towards the central portion of the channel region and decreases toward the source and drain regions.

With regard to Claim 12, Applicant claims that "the non-uniform concentration is formed by a tilted ion implantation utilizing as a mask at least part of a gate structure of said transistor." This a product by process limitation. A "product by process" claim is directed to the product per se, no matter how actually made, In re Brown, 173 USPQ 685; In re Luck, 177 USPQ 523; In re Fessmann, 180 USPQ 324; In re Avery, 186 USPQ 161; In re Wertheim, 191 USPQ 90 (209 USPQ 554 does not deal with this issue); In re Marosi et al, 218 USPQ 289; and particularly In re Thorpe, 227 USPQ 964, all of which make it clear that it is the patentability of the final product per se which must be determined in a "product by process" claim, and not the patentability of the process, and that an old or obvious product produced by a new method is not patentable as a product, whether claimed in "product by process" claims or not. Note that applicant has the burden of proof in such cases, as the above case law makes clear.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Edgardo Ortiz (Art Unit 2815), whose telephone number is (703) 308-6183. In case the Examiner can not be reached by a direct telephone call, you might call Supervisor Eddie Lee at (703) 308-1690. Any inquiry of a general nature or relating to the status of this application should be directed to the Group 2800 receptionist whose telephone number is (703) 308-0956.

EO / AU 2815

10/19/01

EDDIE LEE SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800